Fig. 1

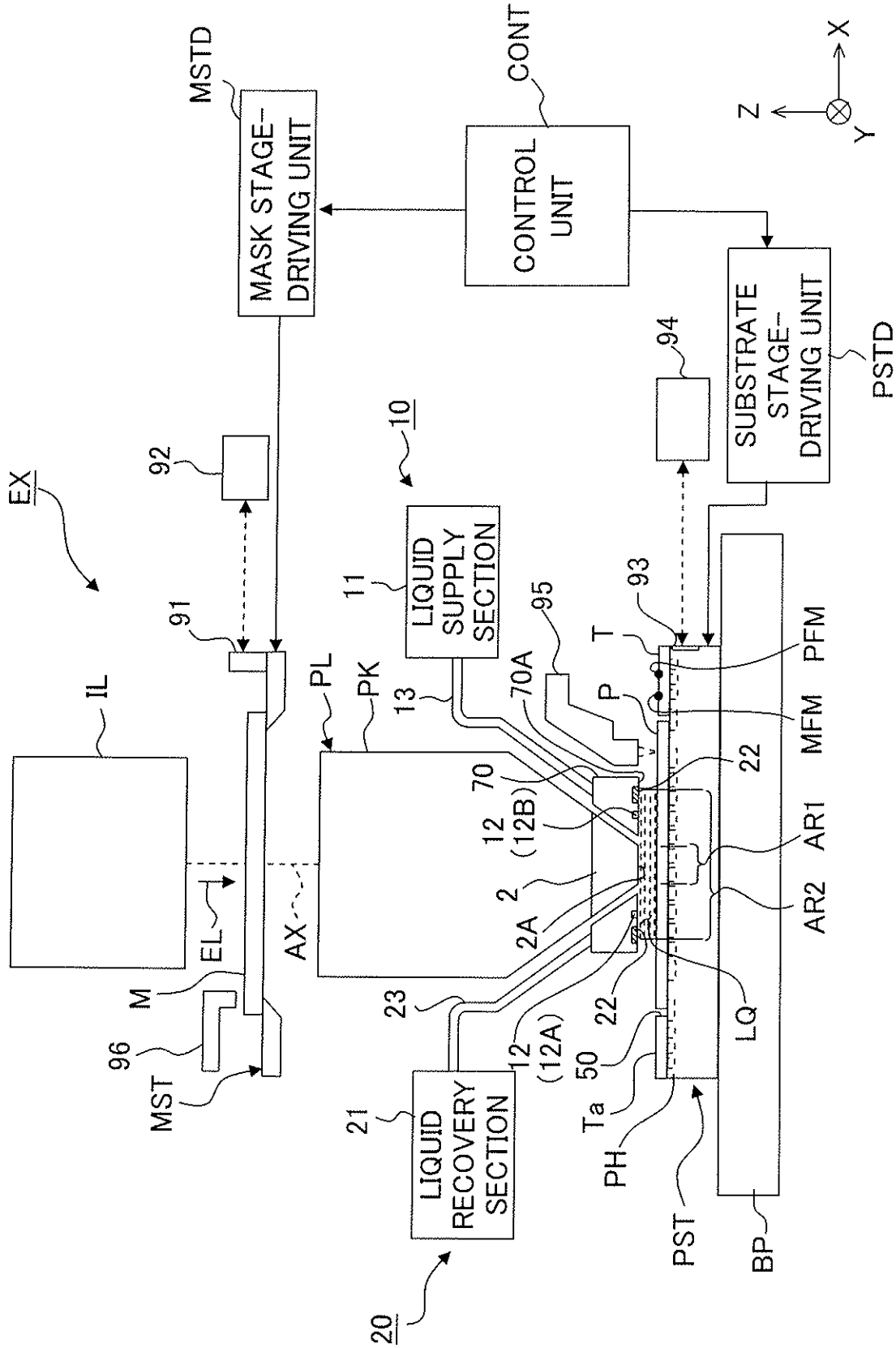
MSTD
MASK STAGE-DRIVING UNIT
CONT
CONTROL UNIT
SUBSTRATE STAGE-DRIVING UNIT
PSTD
Z
X
Y
EX
92
91
IL
M
EL
96
MST
AX
PL
PK
10
11
LIQUID SUPPLY SECTION
13
70A
95
70
12 (12B)
2
2A
23
12 (12A)
21
LIQUID RECOVERY SECTION
20
94
93
T
P
PFM
MFM
22
AR1
AR2
LQ
50
Ta
PH
PST
BP

Fig. 2

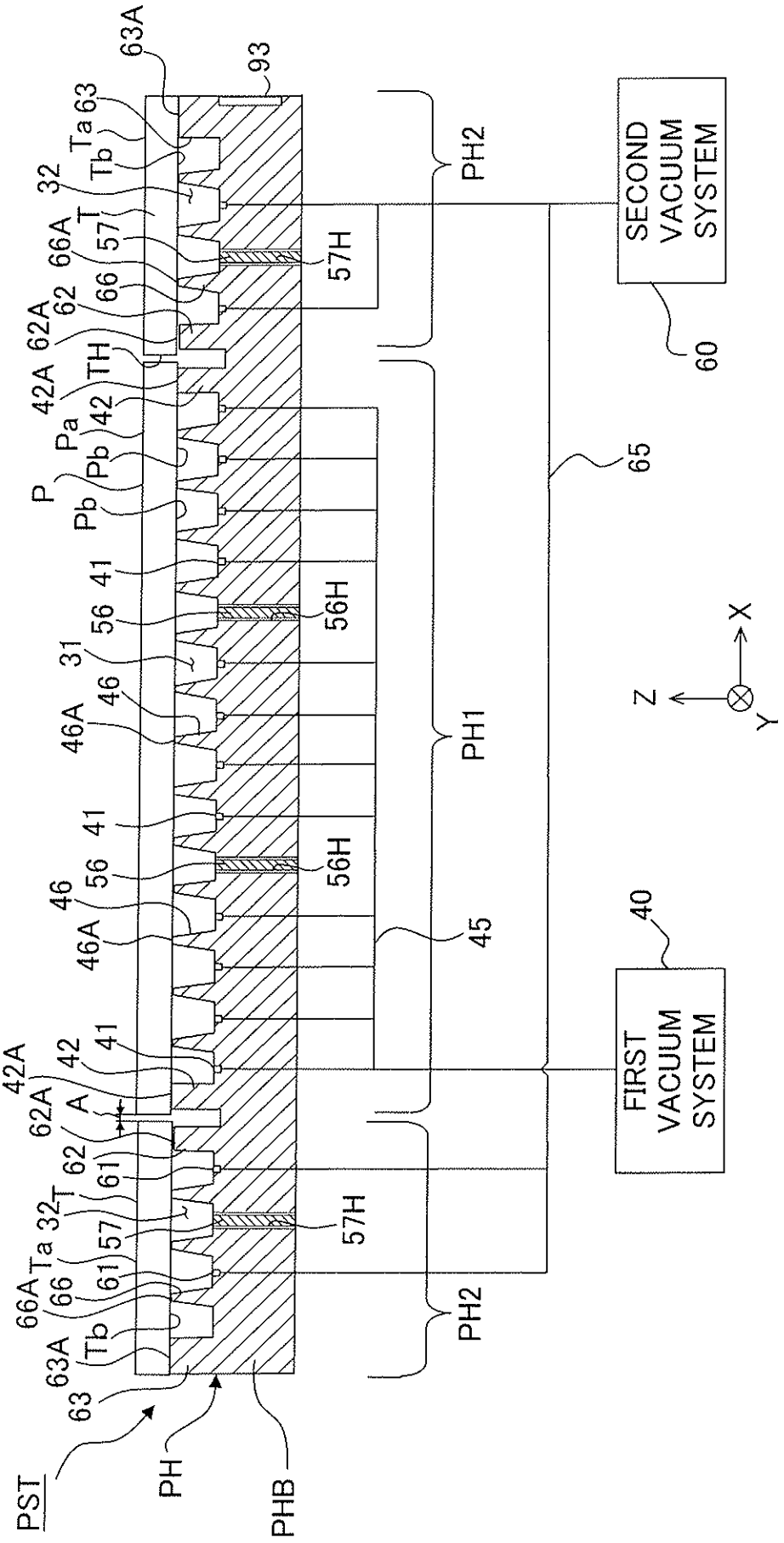
PST
PH
PHB
63
63A
93
Ta
Tb
32
T
57
66A
66
62
62A
TH
42A
42
Pa
Pb
P
41
56
31
46
46A
61
A
57H
56H
PH1
PH2
45
65
60
40
SECOND VACUUM SYSTEM
FIRST VACUUM SYSTEM
X
Y
Z

Fig. 3

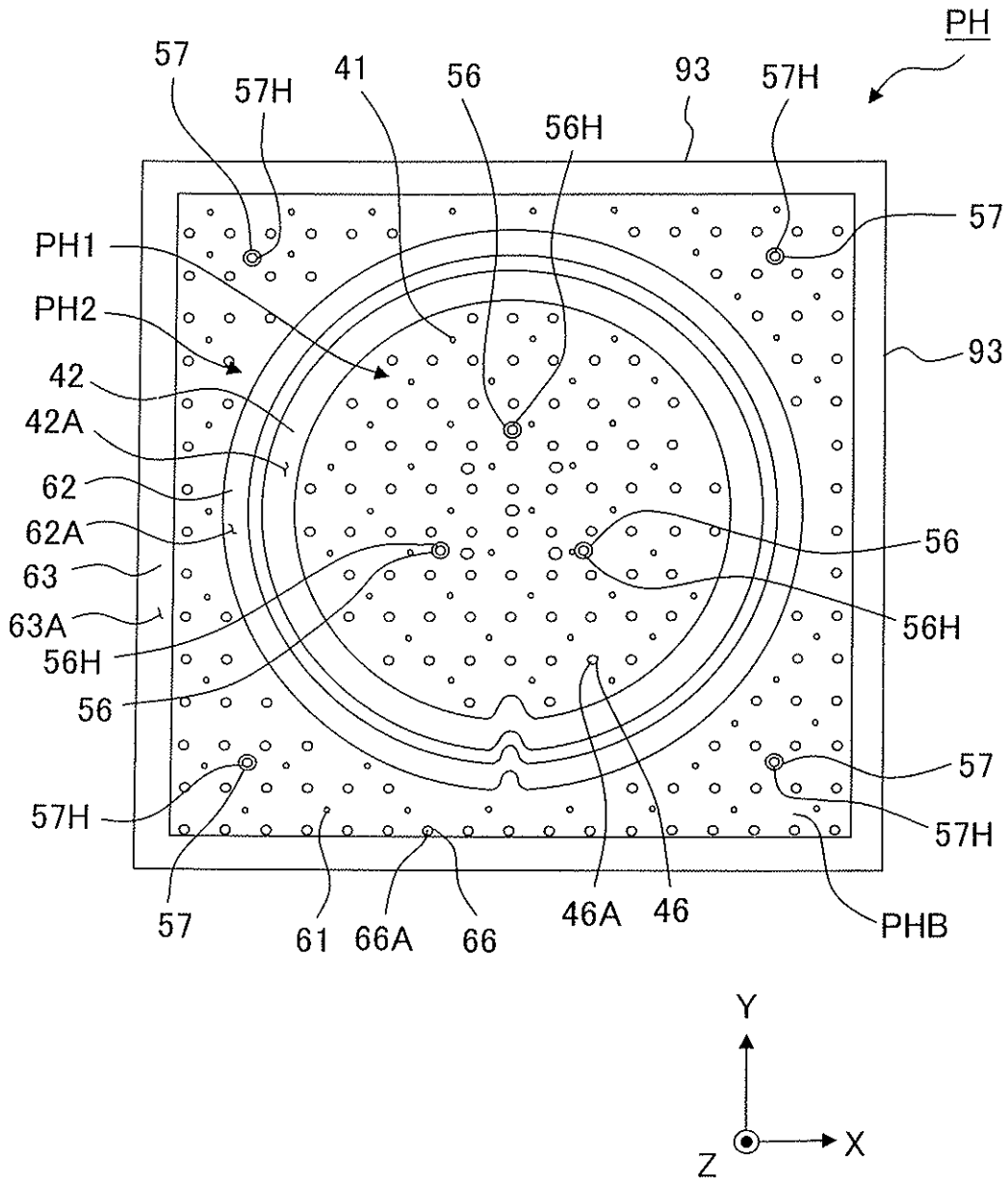
PH
57
57H
41
56
93
57H
56H
57
PH1
PH2
93
42
42A
62
62A
56
63
56H
63A
56H
56
57H
57
57H
57
61
66A
66
46A
46
PHB
Y
Z
X

Fig. 4

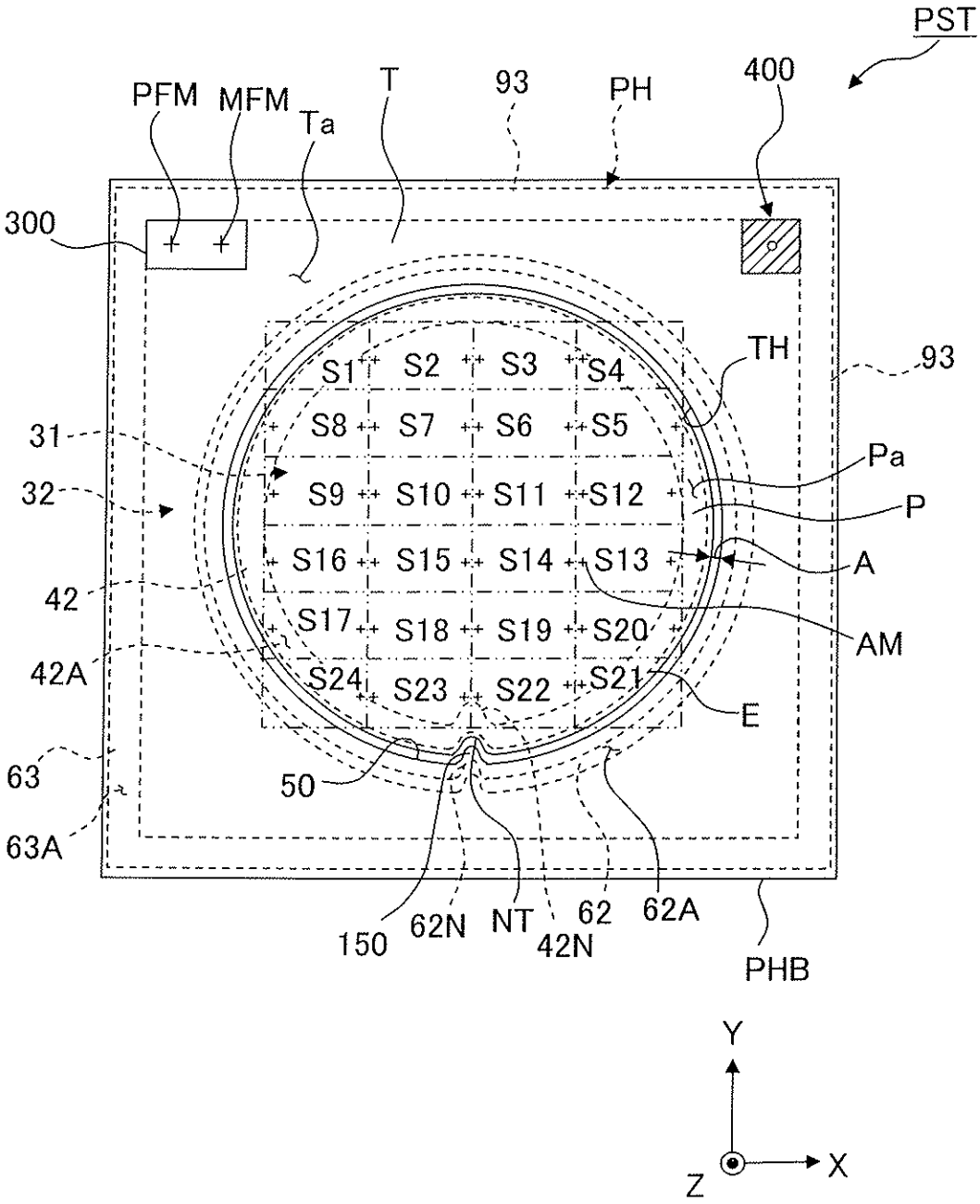
PST
PFM
MFM
Ta
T
93
PH
400
300
TH
93
S1
S2
S3
S4
S8
S7
S6
S5
S9
S10
S11
S12
S16
S15
S14
S13
S17
S18
S19
S20
S24
S23
S22
S21
31
32
42
42A
63
63A
Pa
P
A
AM
E
50
150
62N
NT
42N
62
62A
PHB
Y
X
Z

Fig. 5

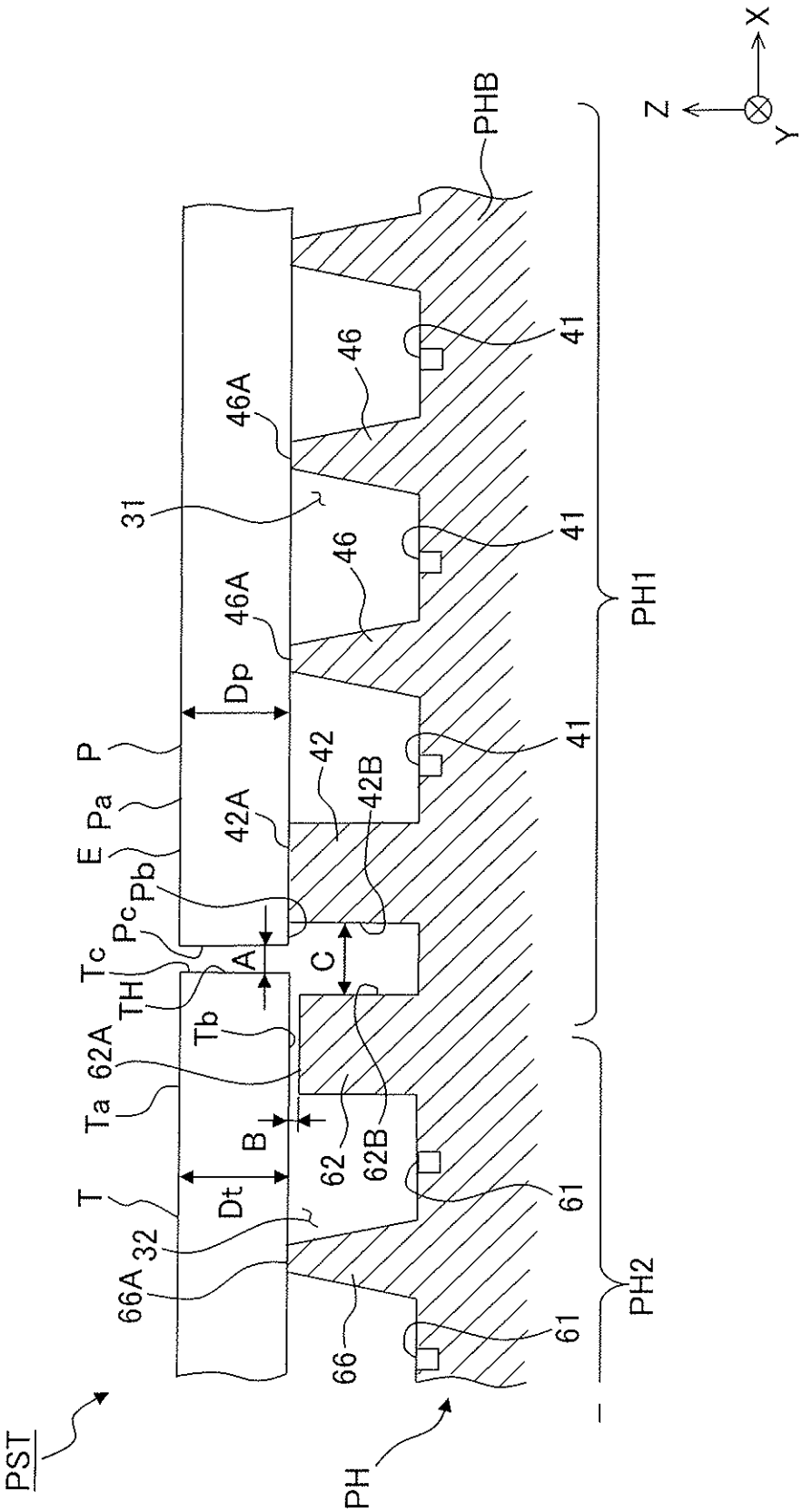
PST
PH
PH1
PH2
PHB
T
Ta
Tb
Tc
TH
Pa
Pb
Pc
E
P
Dt
Dp
A
B
C
31
32
41
42
42A
42B
46
46A
61
62
62A
62B
66
66A
X
Y
Z

Fig. 6

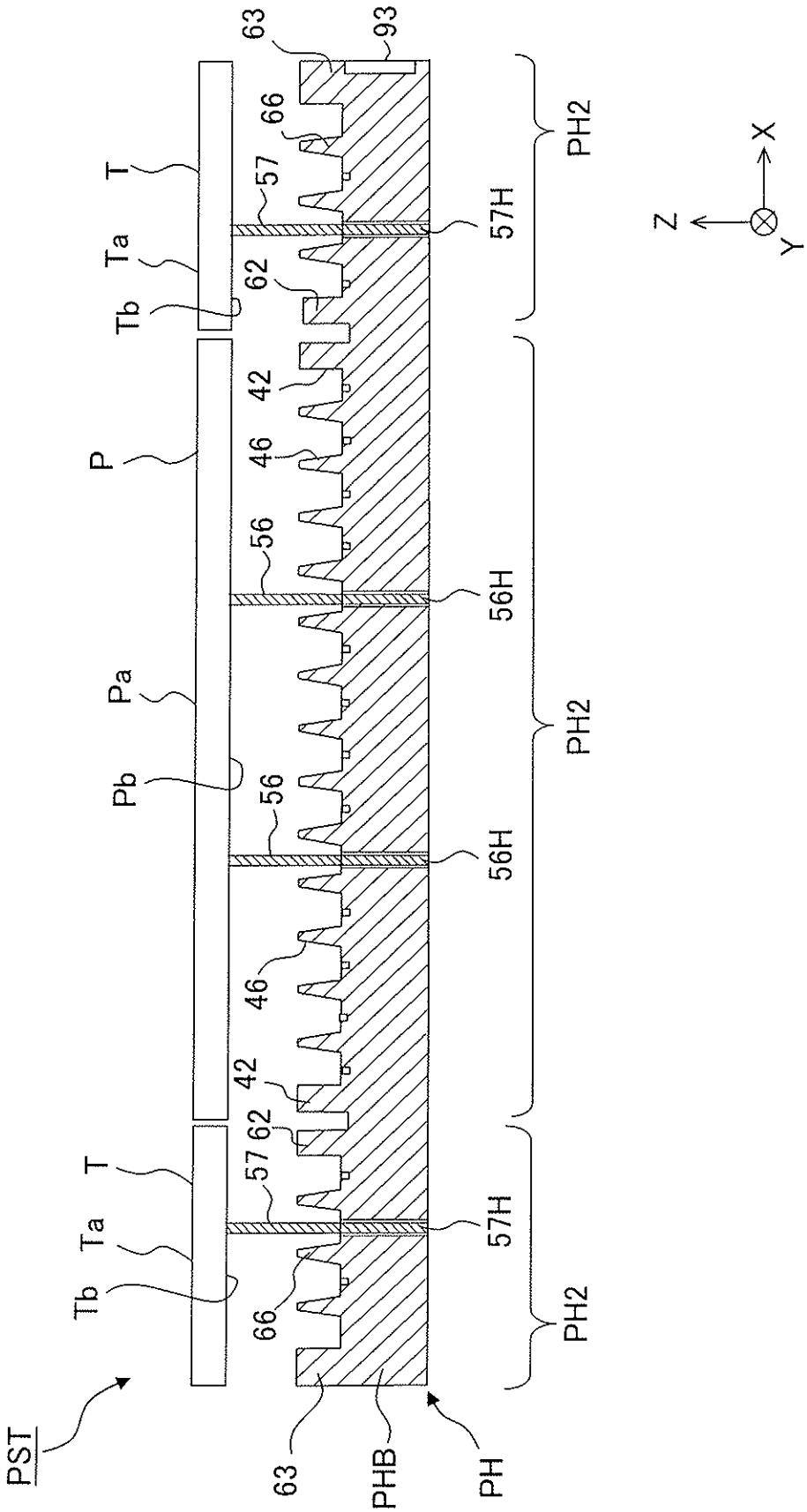

Fig. 7

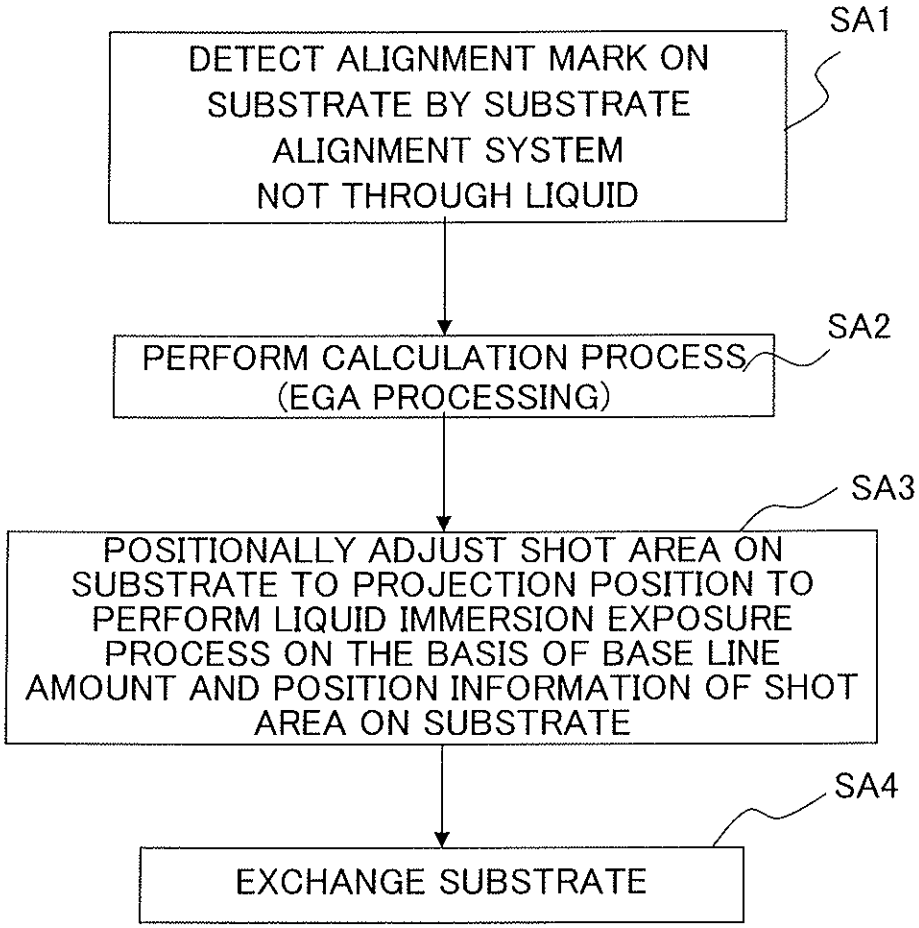
SA1
DETECT ALIGNMENT MARK ON SUBSTRATE BY SUBSTRATE ALIGNMENT SYSTEM NOT THROUGH LIQUID
SA2
PERFORM CALCULATION PROCESS (EGA PROCESSING)
SA3
POSITIONALLY ADJUST SHOT AREA ON SUBSTRATE TO PROJECTION POSITION TO PERFORM LIQUID IMMERSION EXPOSURE PROCESS ON THE BASIS OF BASE LINE AMOUNT AND POSITION INFORMATION OF SHOT AREA ON SUBSTRATE
SA4
EXCHANGE SUBSTRATE

Fig. 8

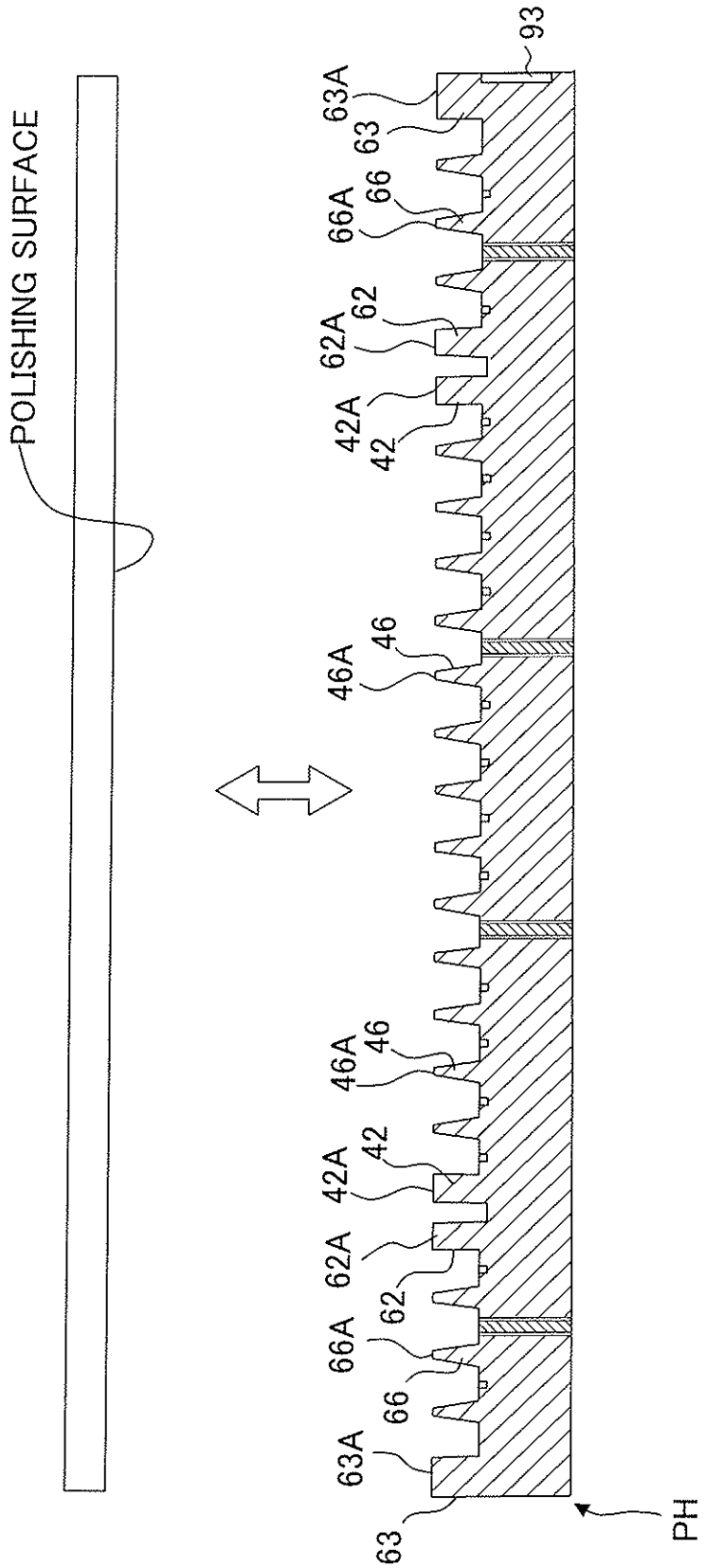
POLISHING SURFACE
93
63A
63
66A
66
62A
62
42A
42
46A
46
46A
46
42A
42
62A
62
66A
66
63A
63
PH

Fig. 9

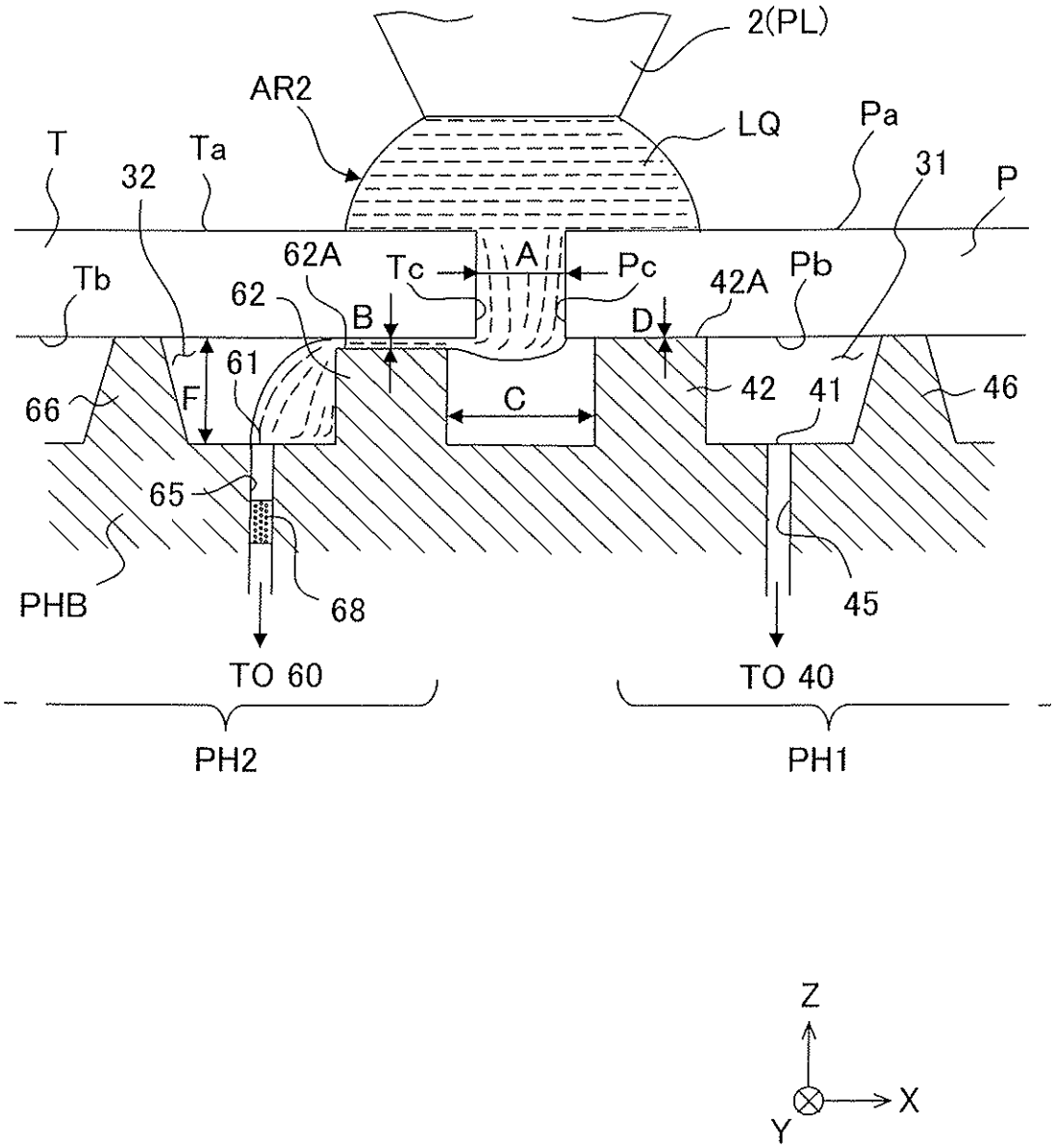
2(PL)
AR2
LQ
Pa
T
Ta
32
31
P
Tb
62A
Tc
A
Pc
42A
Pb
62
B
D
61
F
C
42
41
46
66
65
PHB
68
45
TO 60
TO 40
PH2
PH1
Z
X
Y

Fig. 10

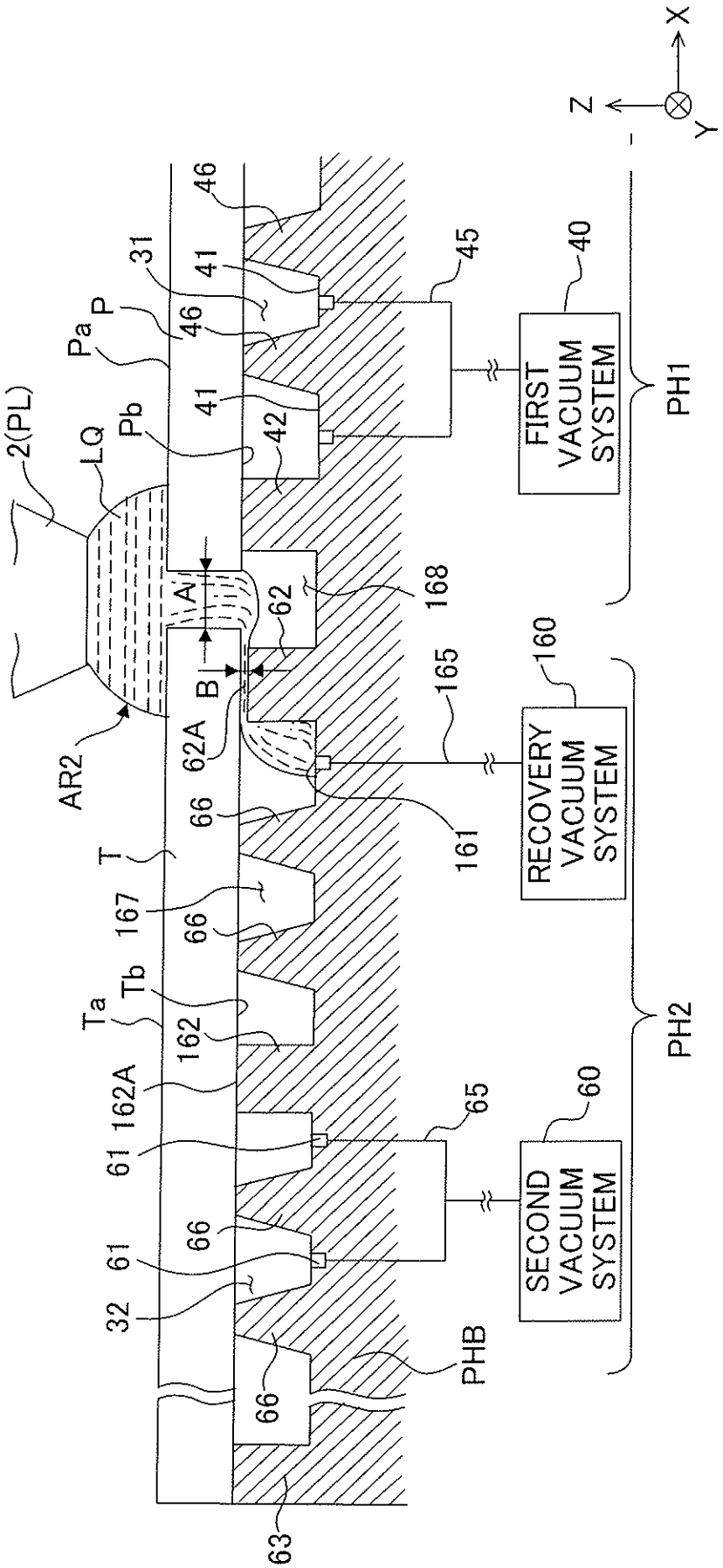
X
Z
Y
2(PL)
LQ
AR2
T
Ta
Tb
Pa
P
Pb
A
B
31
41
46
42
45
40
FIRST VACUUM SYSTEM
PH1
62
62A
168
165
160
RECOVERY VACUUM SYSTEM
161
66
167
162
162A
61
65
60
SECOND VACUUM SYSTEM
PH2
32
PHB
63

Fig. 11

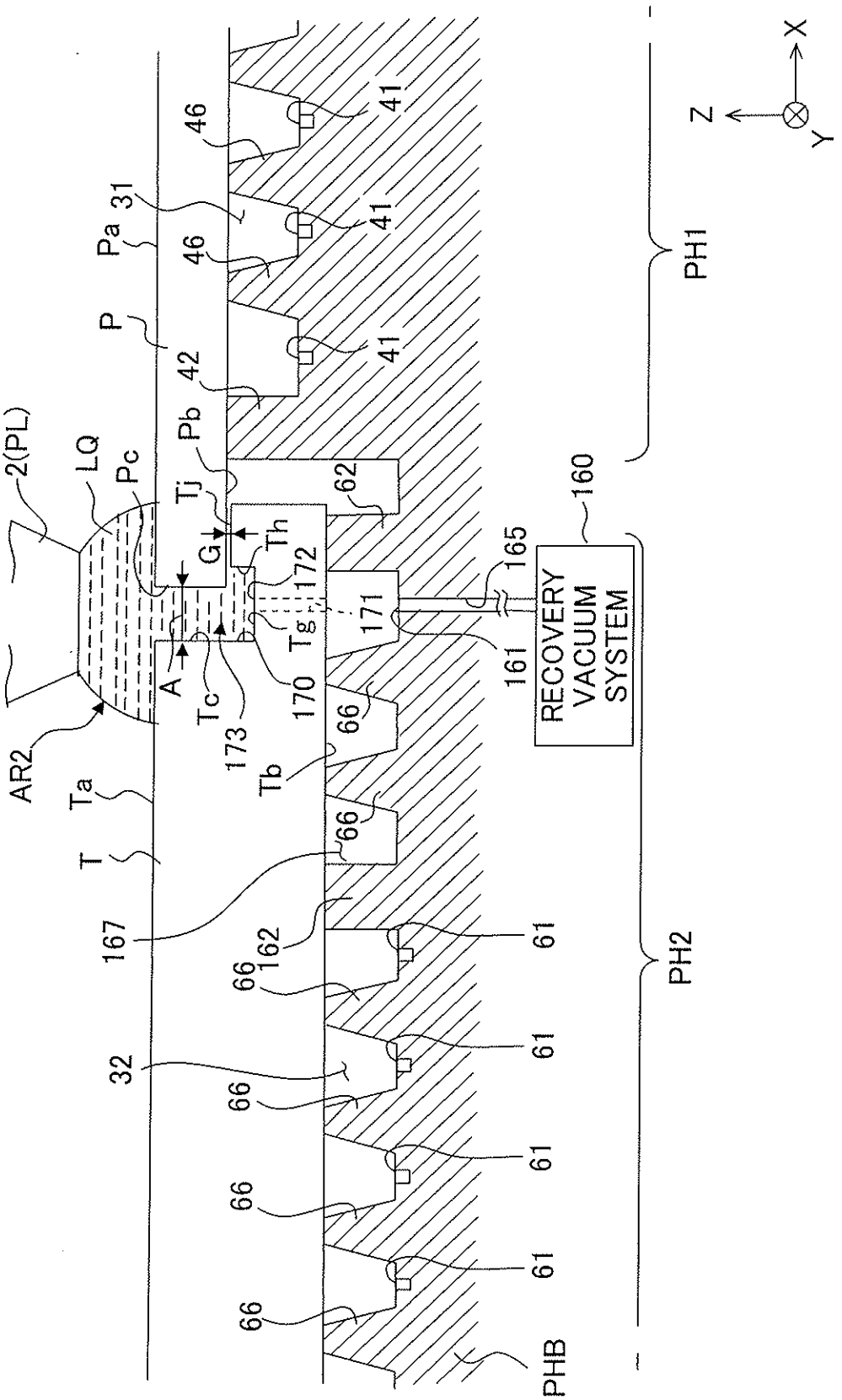
2(PL)
LQ
Pc
Pa
31
P
46
41
42
Pb
Tj
G
Th
172
Tg
171
170
173
Tc
A
AR2
Ta
T
Tb
62
66
165
161
160
RECOVERY VACUUM SYSTEM
167
162
61
32
PHB
PH1
PH2
Z
X
Y

Fig. 12

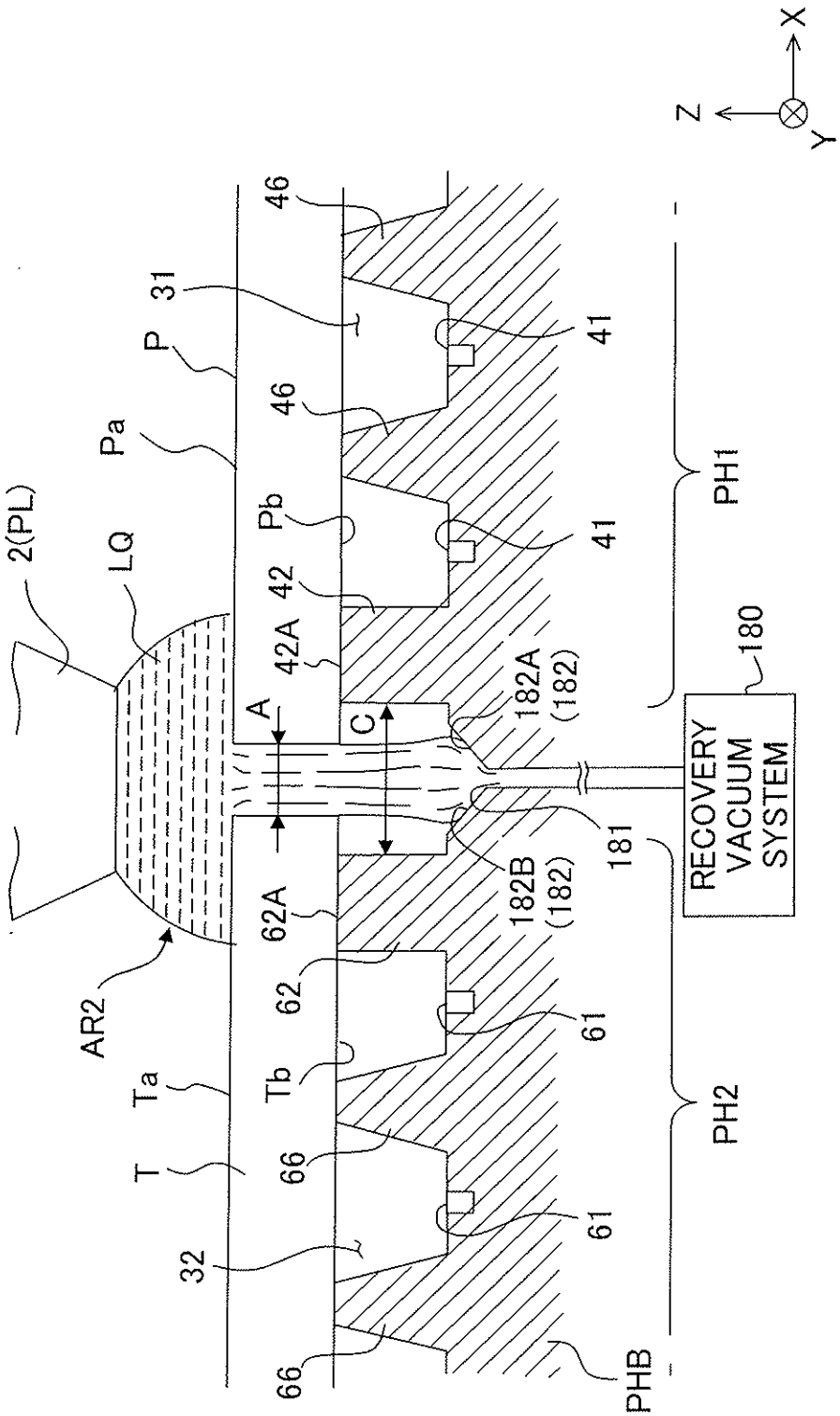
Z
X
Y
2(PL)
LQ
AR2
T
Ta
Tb
Pa
P
Pb
A
C
31
32
46
41
42
42A
62
62A
66
61
182A
(182)
182B
(182)
181
180
RECOVERY
VACUUM
SYSTEM
PH1
PH2
PHB

Fig. 13

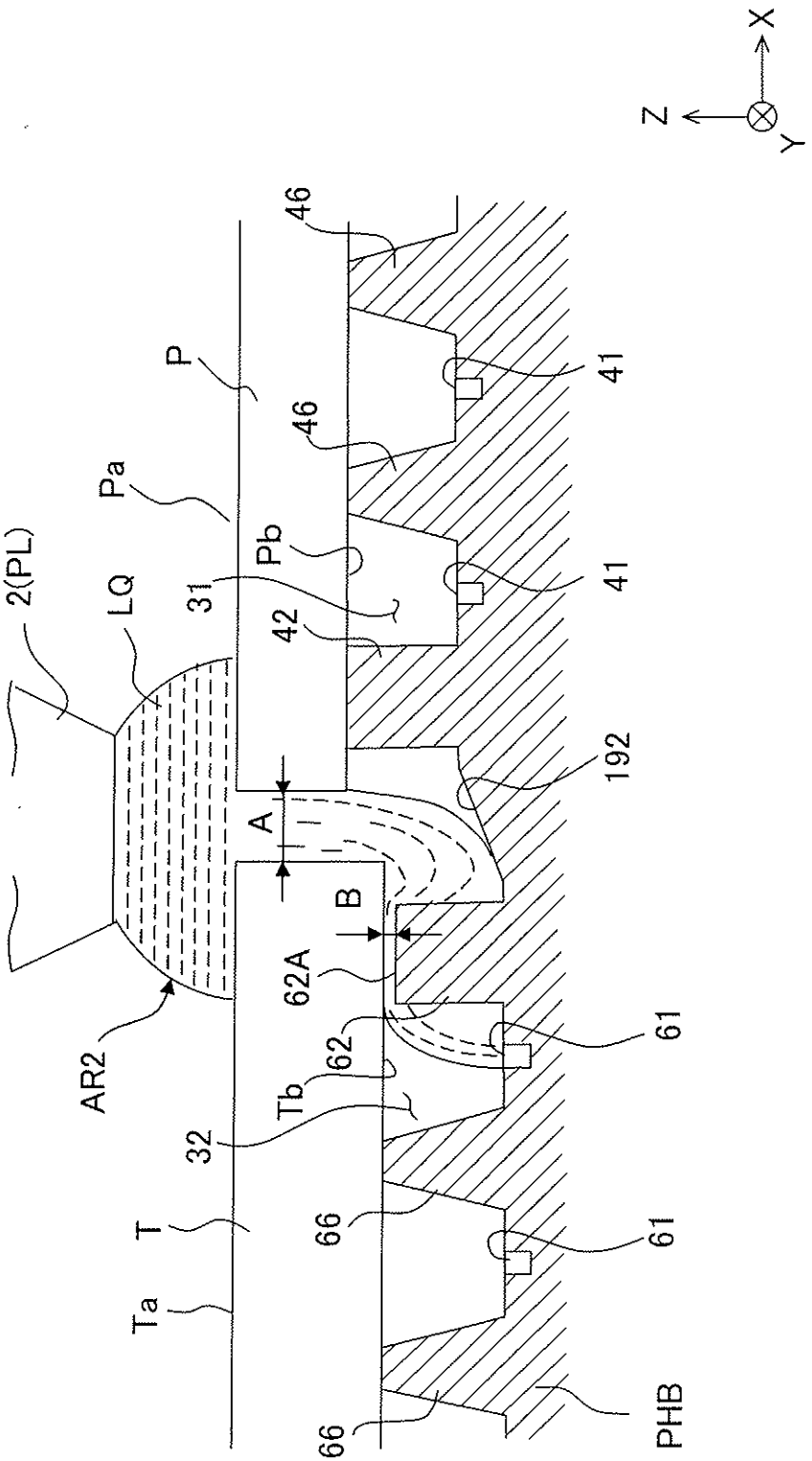
X
Z
Y
46
P
41
46
Pa
Pb
41
2(PL)
LQ
31
42
192
A
B
62A
61
AR2
62
Tb
32
66
61
T
Ta
66
PHB

Fig. 14

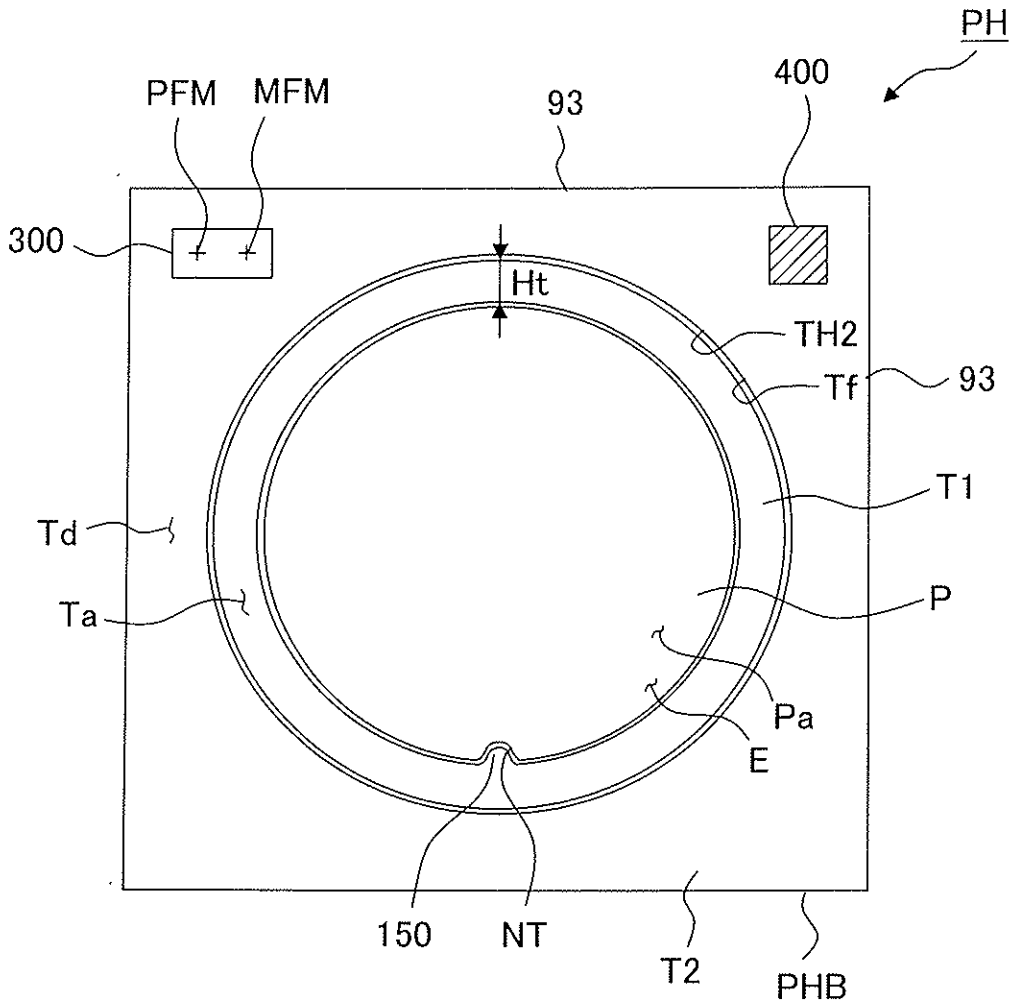

Fig. 15

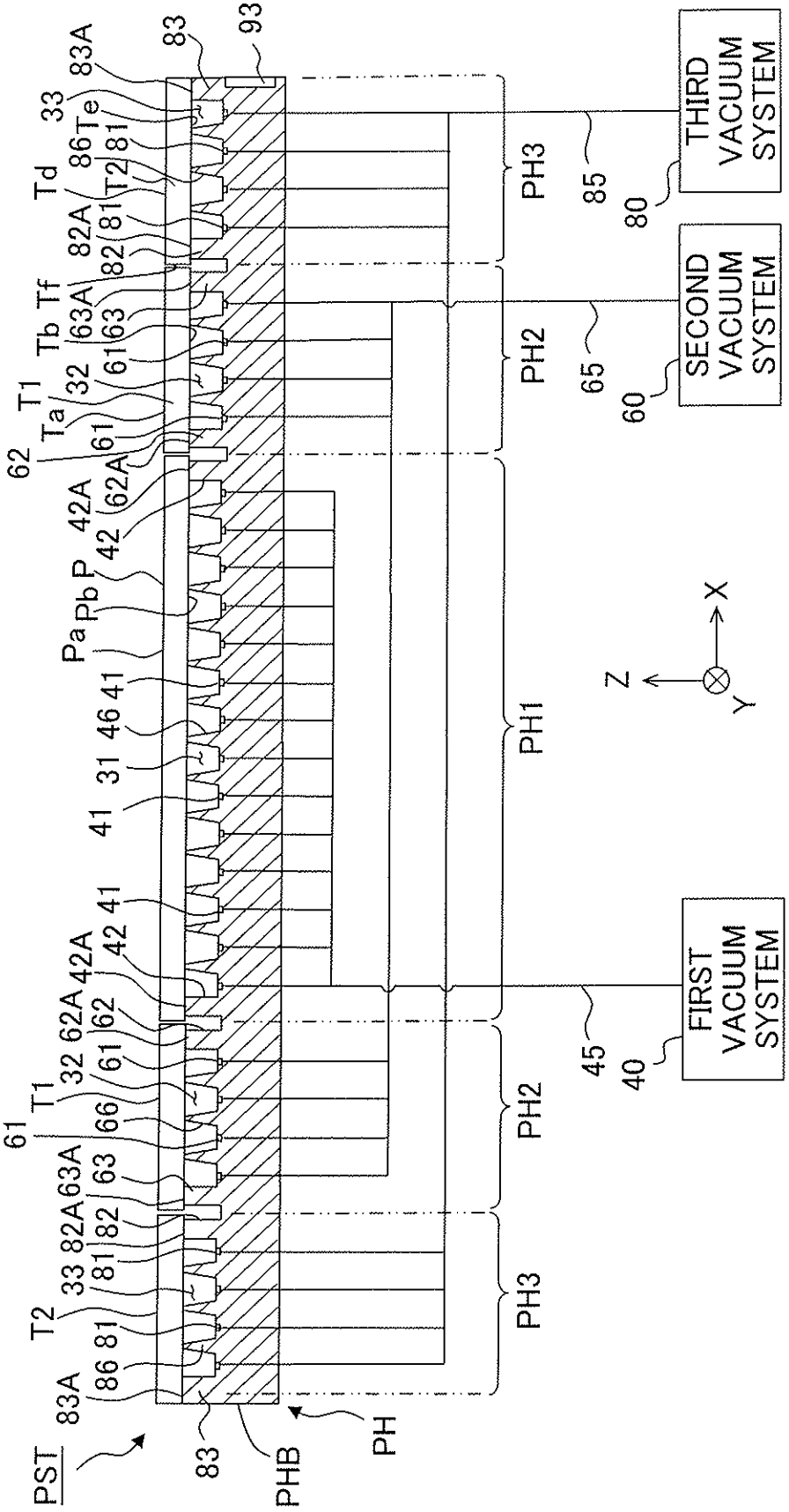
PST
83A
86
81
T2
33
82A
81
82
63A
63
66
61
T1
32
62A
62
61
42A
42
41
41
31
46
41
Pa
Pb
P
42
42A
62A
61
62
Ta
T1
32
61
Tb
Tf
63A
63
82A
81
82
Td
T2
86
81
33
Te
83A
83
93
83
PHB
PH
PH3
PH2
PH1
PH2
PH3
45
40
FIRST VACUUM SYSTEM
65
60
SECOND VACUUM SYSTEM
85
80
THIRD VACUUM SYSTEM
X
Z
Y

Fig. 16

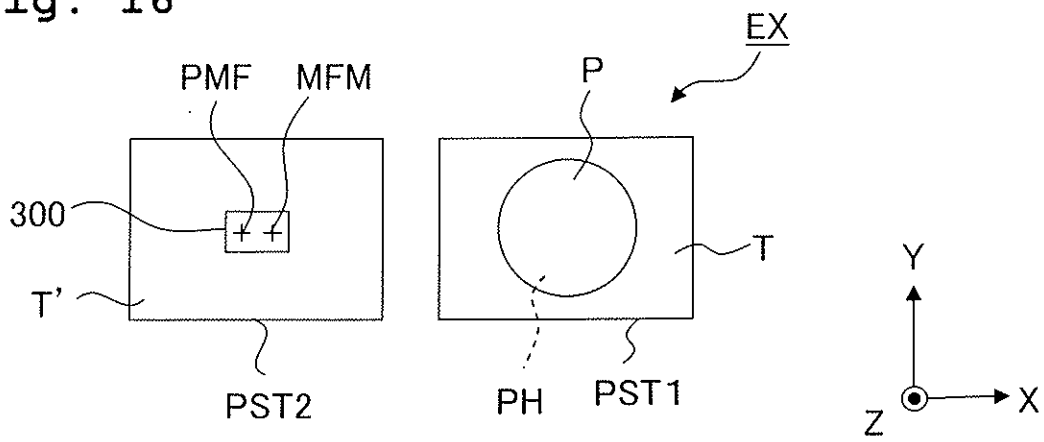
EX
PMF
MFM
P
300
T
T'
Y
PST2
PH
PST1
Z
X

Fig. 17

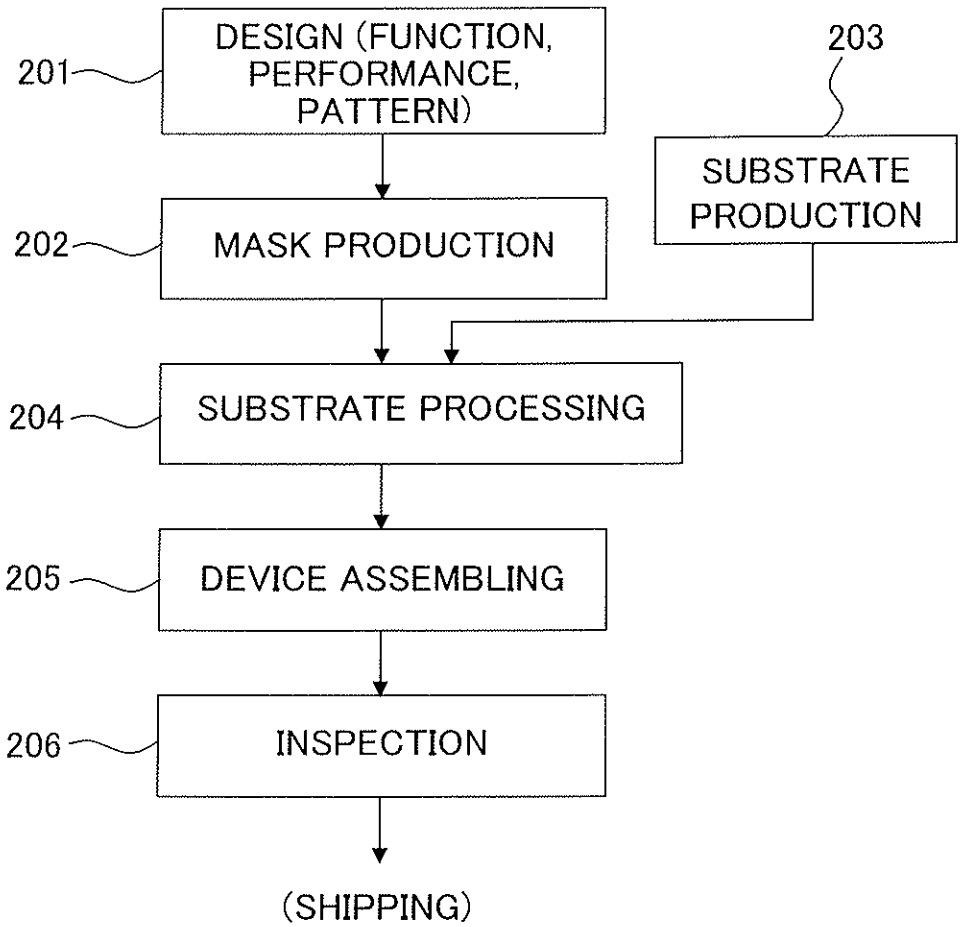
201
DESIGN (FUNCTION, PERFORMANCE, PATTERN)
203
SUBSTRATE PRODUCTION
202
MASK PRODUCTION
204
SUBSTRATE PROCESSING
205
DEVICE ASSEMBLING
206
INSPECTION
(SHIPPING)

Fig. 18

